



CAVENDISH KINETICS

MEMS and RF

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March 30th, 2010

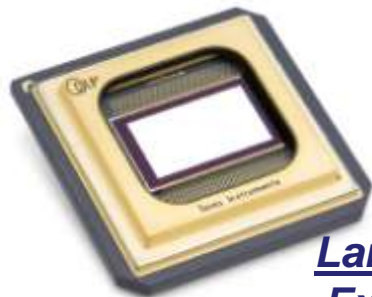
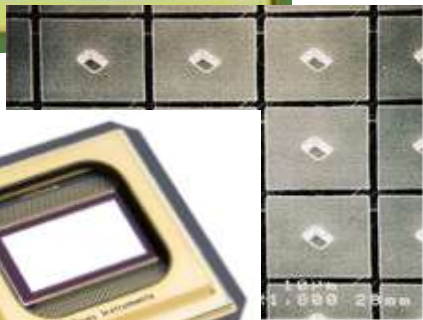
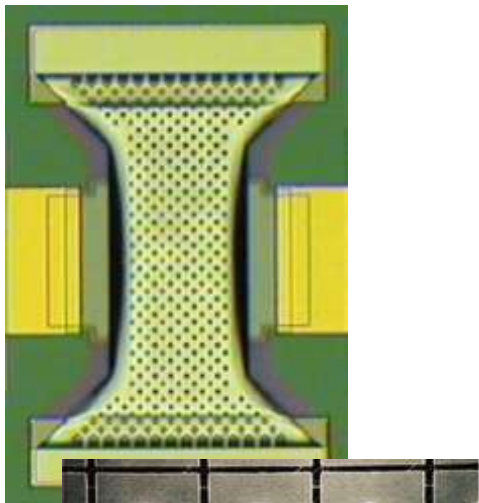


MEMS Technology Trend

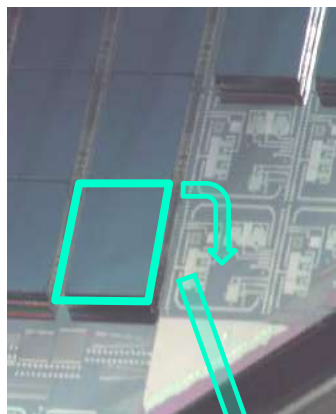
Gen1: Build / Assemble

Gen2: Package in Package

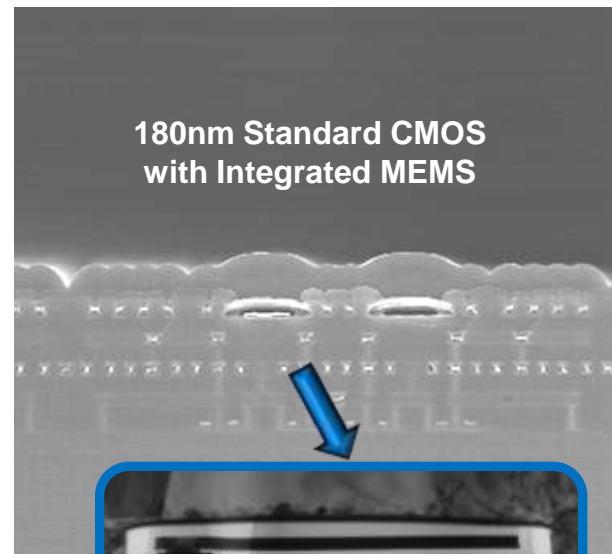
Gen3: Fully Integrated Cavendish 3rd Gen MEMS



Large, Very Expensive



Large, Expensive

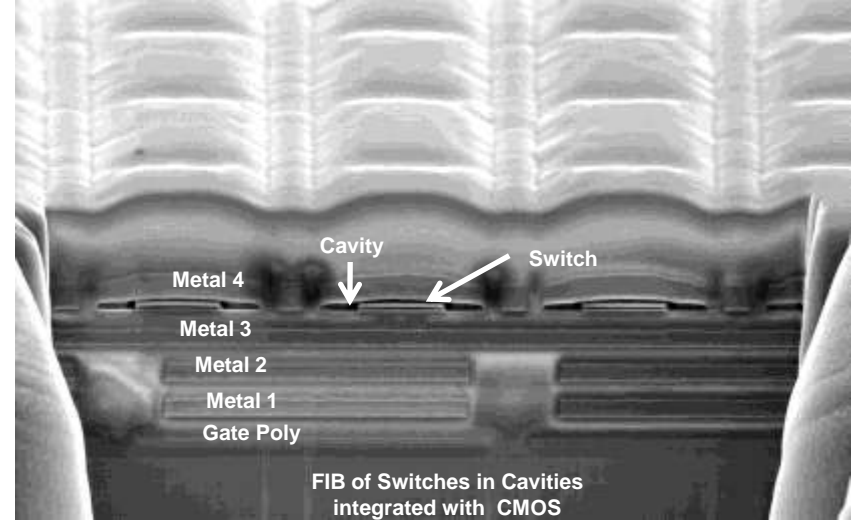
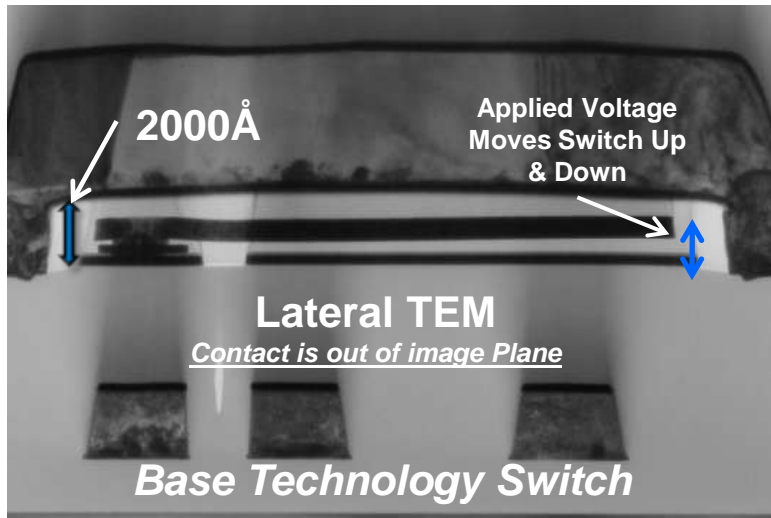


Small, Integrated, Low Cost
No specialized tools/processes/materials

Cavendish MEMS encapsulation provides superior cost & reliability

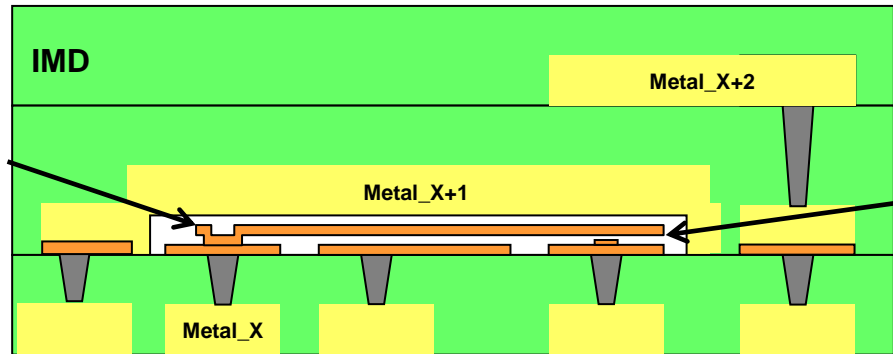


Core Technology: 3rd Gen MEMS



MEMS Technology

- Metal Based MEMS
- Cantilevers
 - Metal Logic
 - NV memory
 - Sensors
- Digital Variable Capacitor
 - Robust MEMS Design
 - Compact Routing
 - Small Die Size



Integrates into Standard Flow

Cavity

- Package Free MEMS
- Non Contaminating
- CMOS Processes
- Planarized Interconnect
- Controlled Release Design
- Electrically Active Roof
- Roof: Metal or Dielectric
- Via Electrical Connections

CMOS Compatible Package Free MEMS, Using Standard Interconnect Technology



❖ **Mission: Enable our Customer to Deliver Breakthrough Products**

- *How:* Enable integration of devices and sensors never before possible
- *Results:* Lower cost, lower power and smaller size
- *Means:* Standard semiconductor processing technology

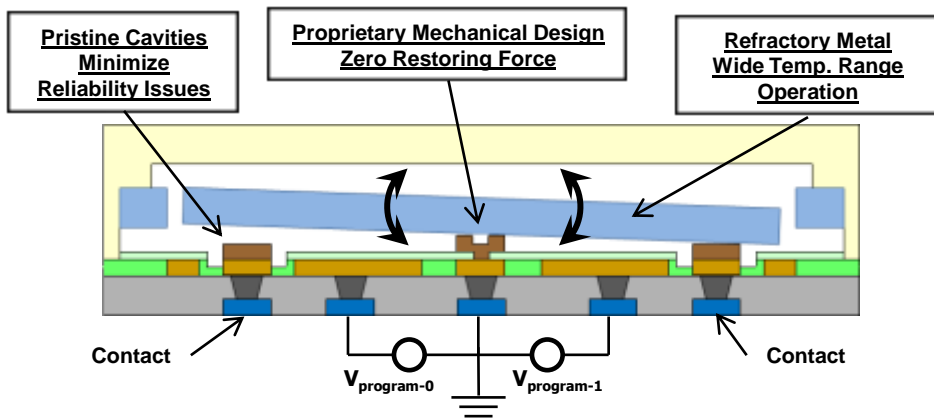
❖ **NanoMech™ Technology Platform – 3rd Generation MEMS**

- Fully integrated into the process flow
- No unique equipment or materials or packaging
- Capability of Delivering Multiple Applications on the same IC

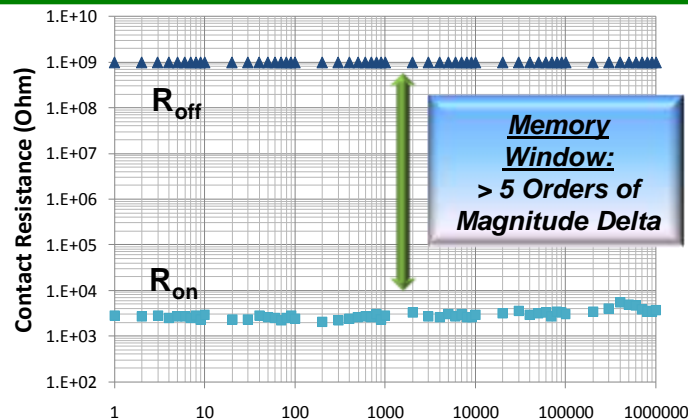
Enable our Customers to Deliver Enhanced Value Products with MEMS Technology



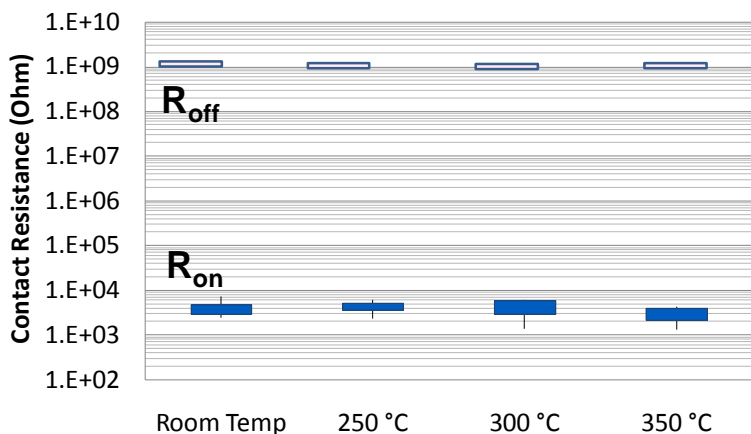
Cavendish Core Design Technology



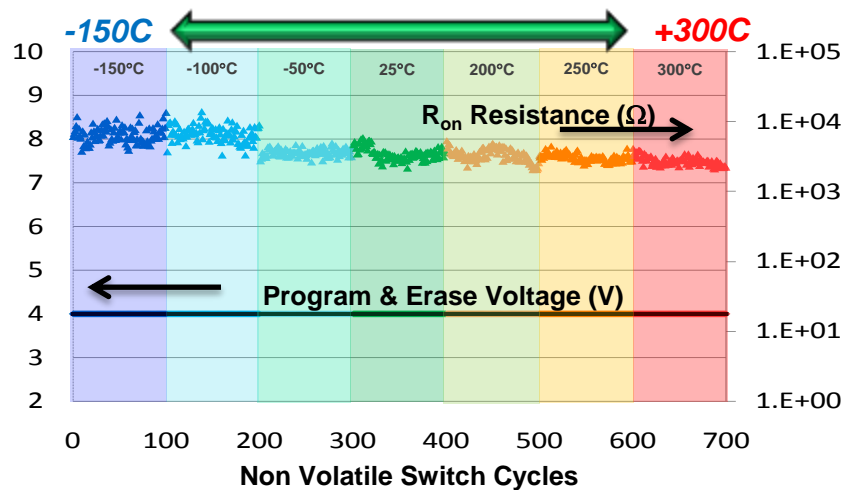
Design Schematic



Performance (No Change in Program / Un Program)



No Effect on Retention vs. Storage Temp up to 350 °C



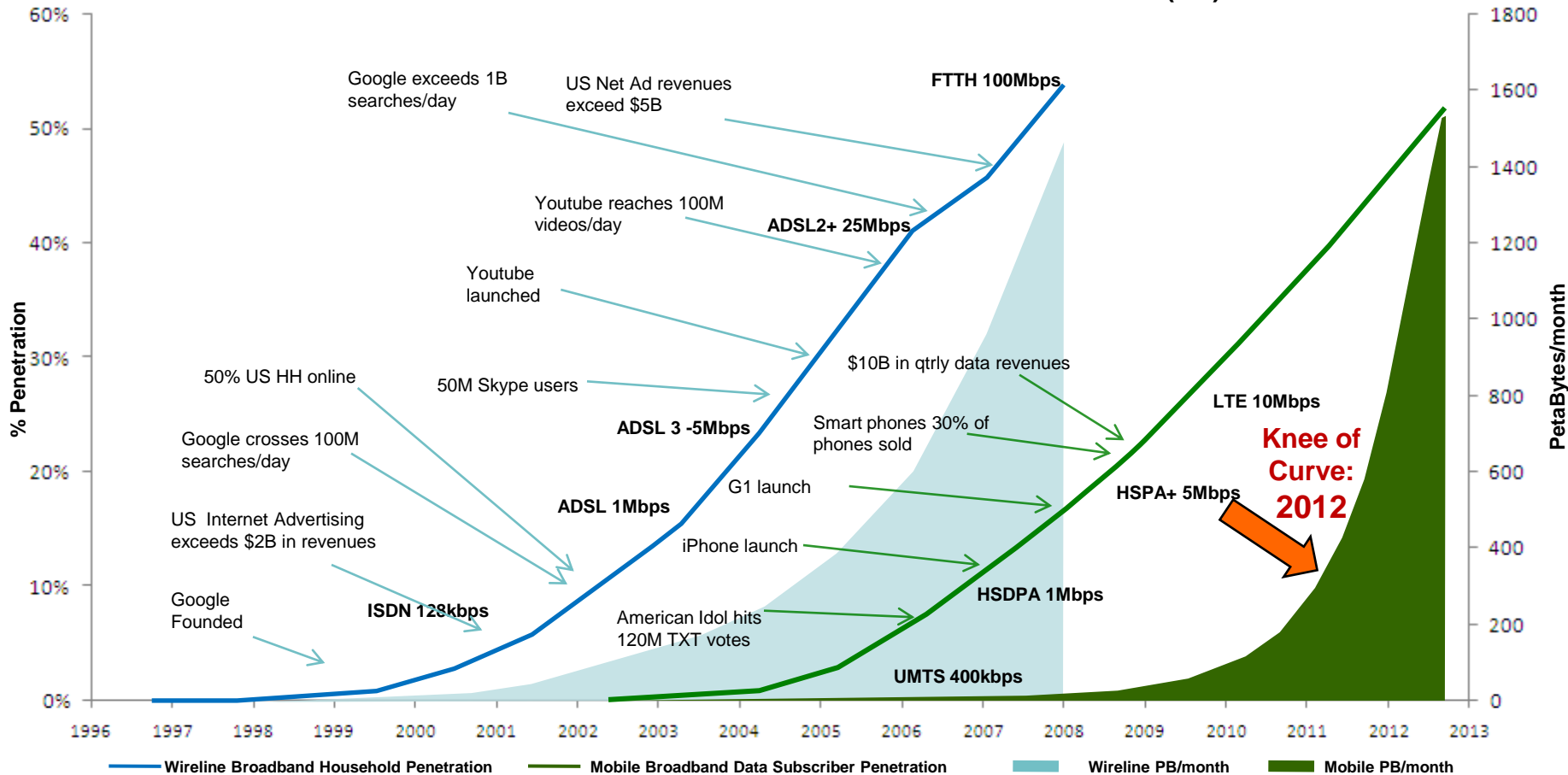
Wide Temperature of Operation -150 °C to +300 °C

NV Switch Performance Demonstrates Robustness of Technology



Data Volume Forecast: Wireless Operators Have a Problem

Broadband Penetration and Traffic for Wireline and Mobile (US)

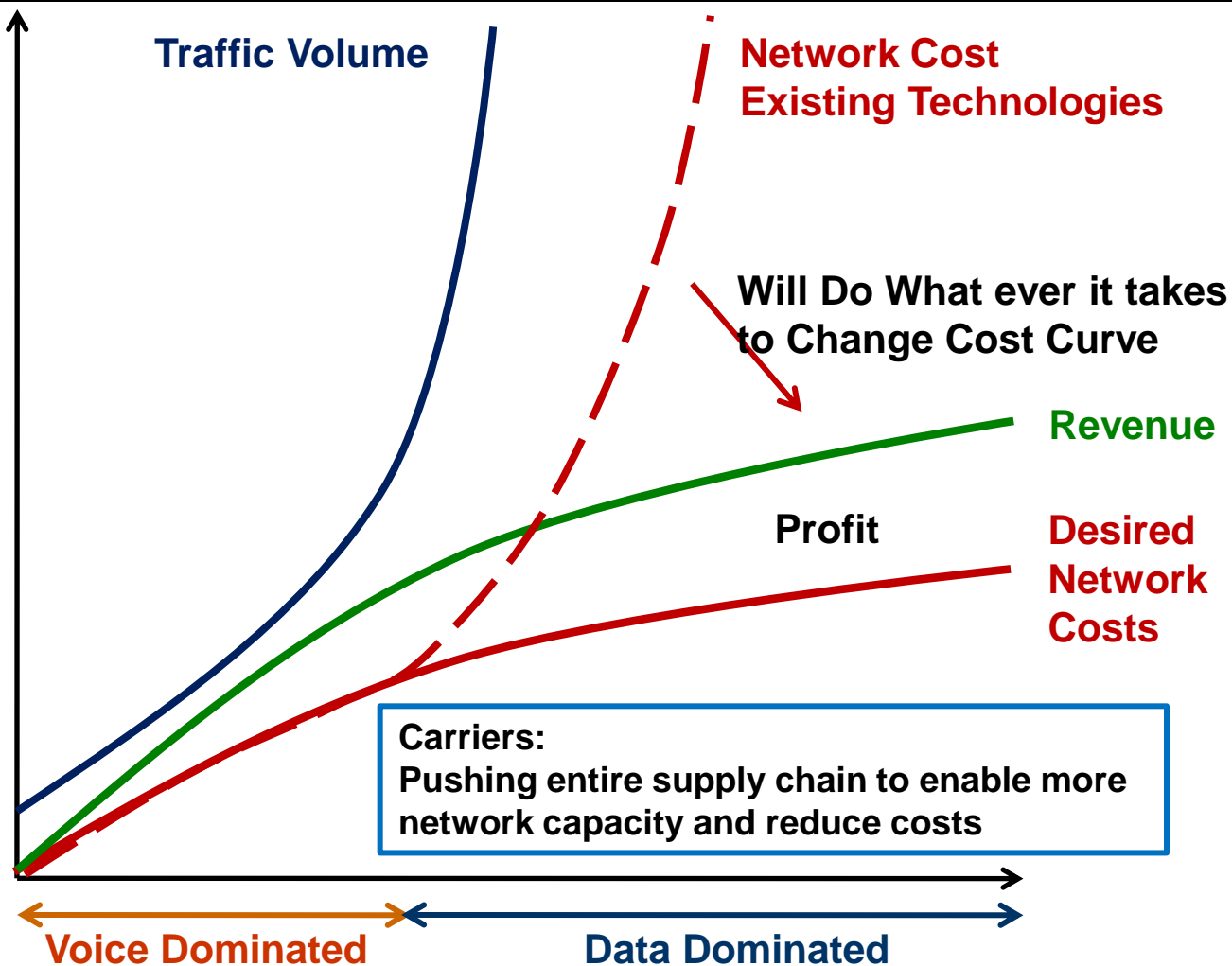


Source: Chetan Sharma Consulting

Wireless devices will need better performance = Opportunity



Carrier Economics Dilemma...



Source: Nokia-Siemens and AT&T

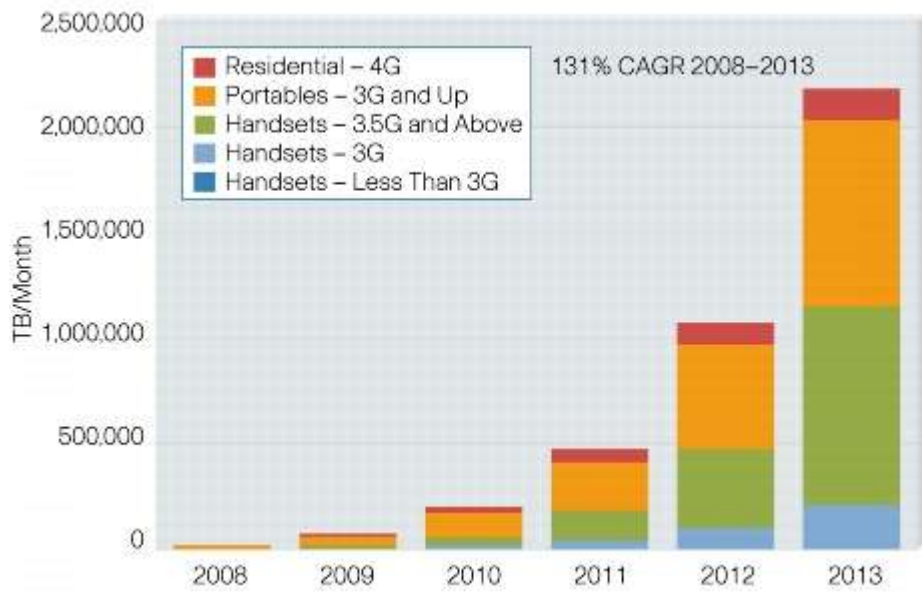
Adding Bands, Adding Complexity, Adding Requirements



What is the Reason and Breakdown...



Uses = 30 Phones of Voice Bandwidth



Data Source: Cisco Systems White Paper Feb 2009

Data is swamping the networks as smart devices are adopted...

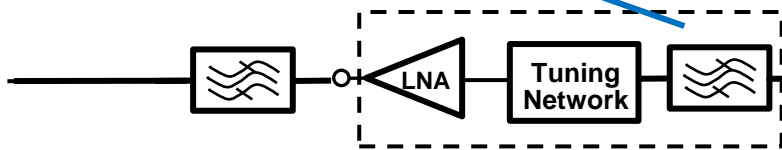


Areas for Applications in FEM

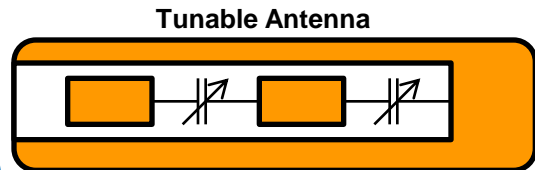
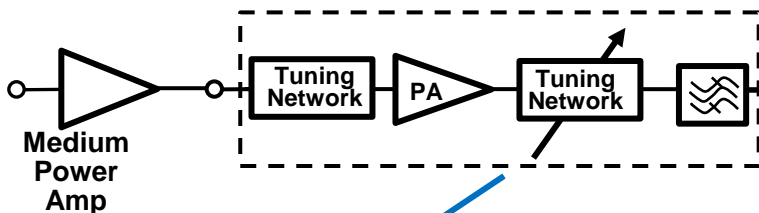
Impedance Matching & Capacitance Loading

Simplified FEM

Future: Tunable Filters



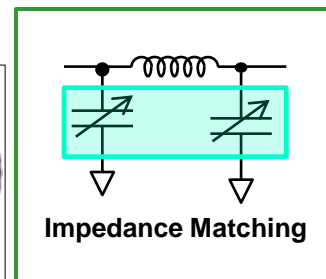
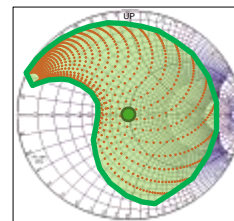
Future: RF Switches



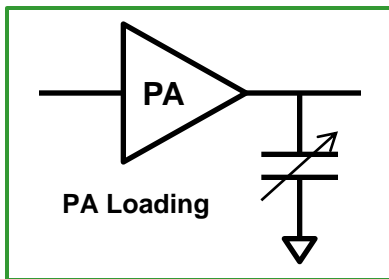
Enables:

Greater Bandwidth
Higher Gain

First Product



Impedance Matching



PA Loading

Enables:

Improved Efficiency at
Multiple frequencies and power levels

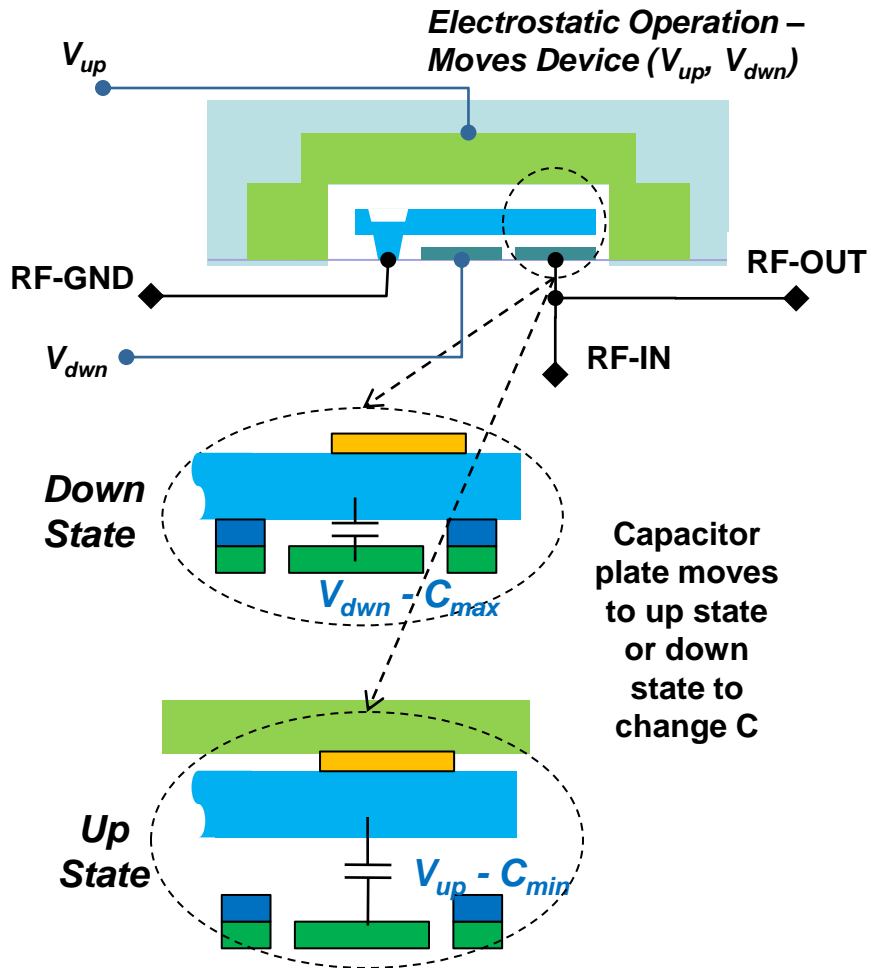
Enables:

Increased Bandwidth, Gain
Reduced Power
Lower System Loss

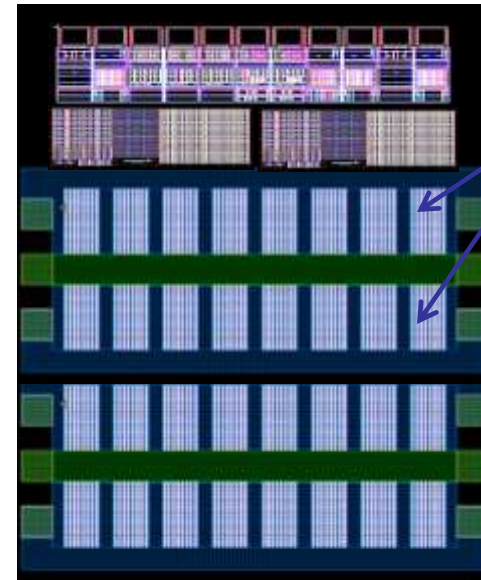
We have the opportunity to Win Multiple Sockets (3 to 5), reducing BOM costs by Multiple Dollars with Smaller Size and Superior Performance

Nanomech™ Based Variable Capacitor Device

CROSS-SECTION VIEW – Unit Cell



Array of Cells – Digital Variable Capacitor



Arrays of capacitors create digitally controlled variable capacitor

Bumped, Bare Die No Package

Variable Capacitor:

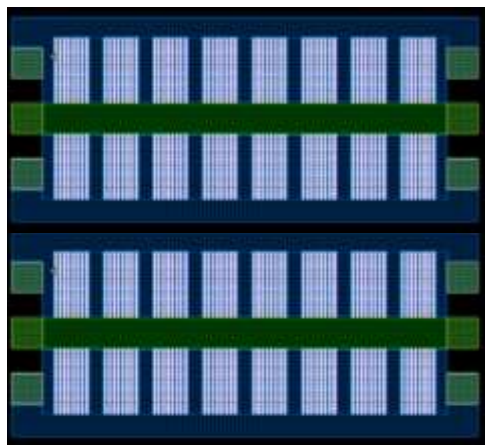
- ✓ Total capacitance is the sum of all the caps
- ✓ Each Capacitor unit individually controlled to be either Up or Down
- ✓ **Result:** High resolution with linear response

Array of Capacitance Switches operated as one Variable Capacitor

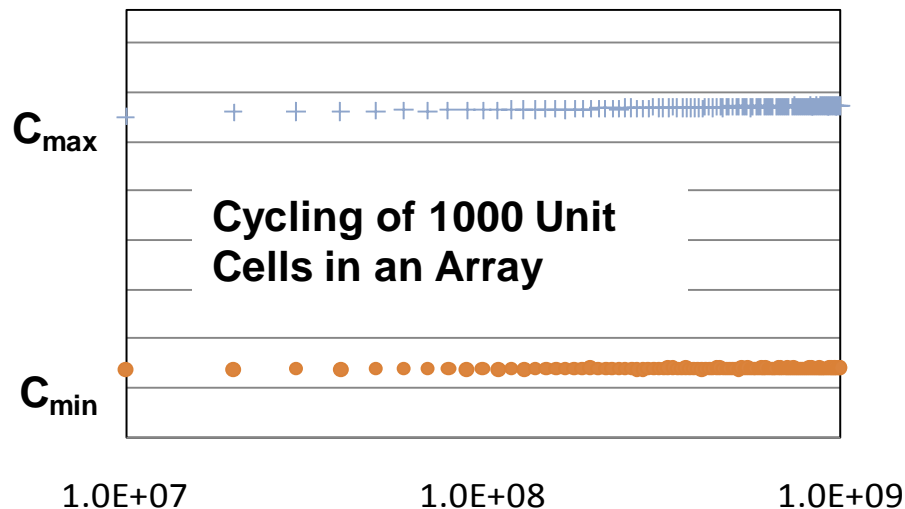


Cavendish Kinetics

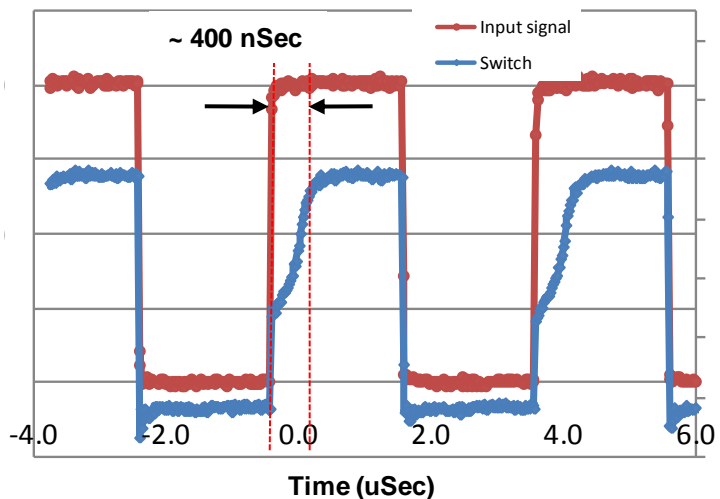
Measured Data



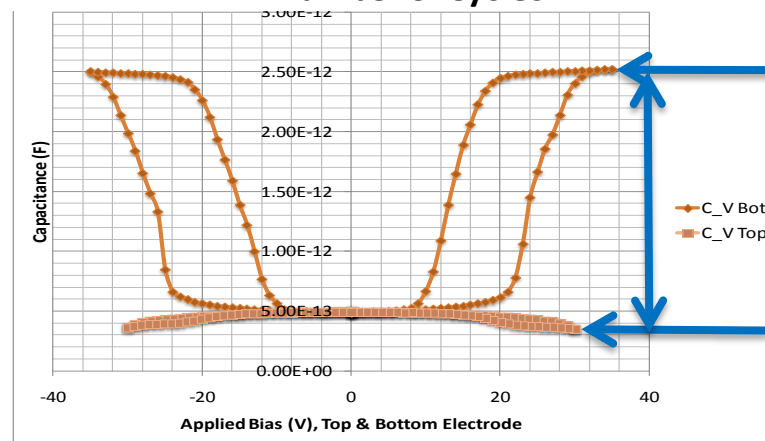
C_{MAX} & C_{MIN} Cycling to 1 Billion Cycles



Capacitor Array Switching Speed



Number of Cycles



Array of “Small Switches” Enables Reliable Fast Variable Capacitor Array



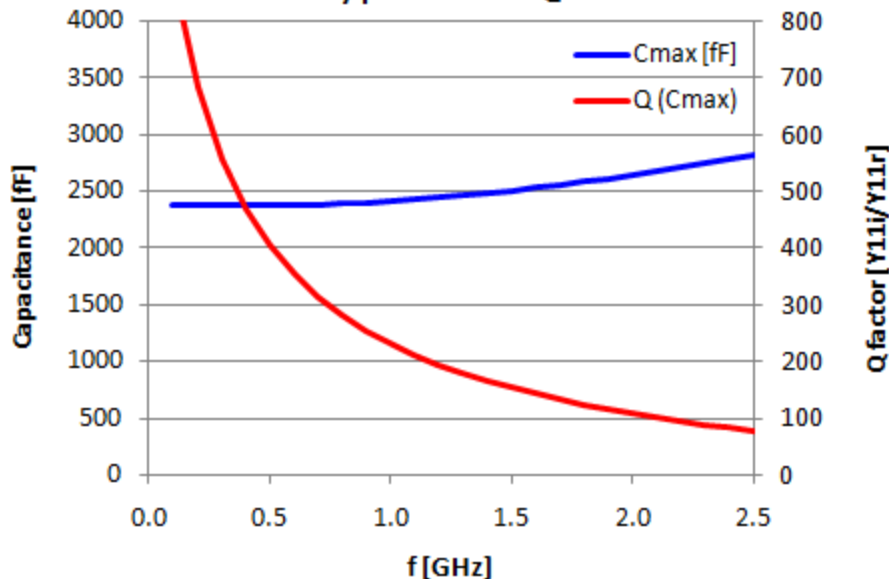
Sample simulation results

(5:1 design)

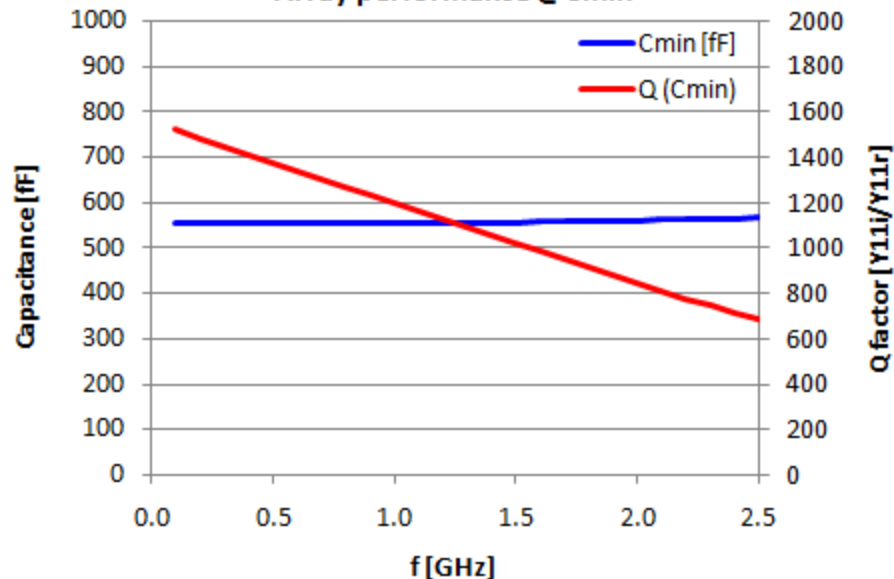
- ❖ **Design example targets:**
 - 5:1 high hot-switch MEMS design (45Vrms)
 - $Q = 100$ at 2GHz
- ❖ **Performance estimate includes effect of bumps and copper traces on RF board (total series inductance ~ 130pH including copper trace on RF board)**

- $Capacitance \equiv Y_{11i}/(2*\pi*f)$
- $Q\ factor \equiv Y_{11i}/Y_{11r}$

Array performance @Cmax

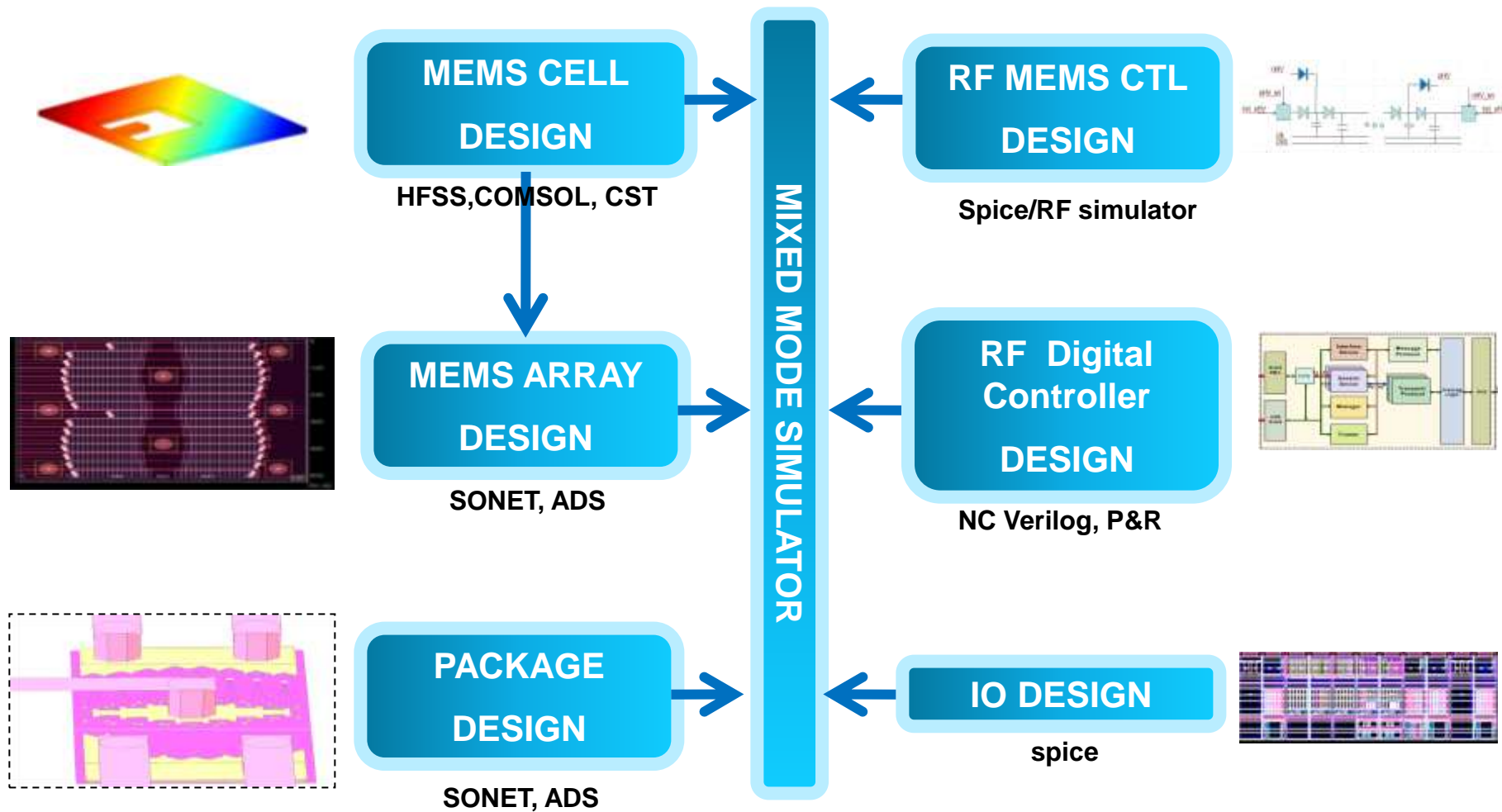


Array performance @Cmin





DVC CAD DESIGN FLOW



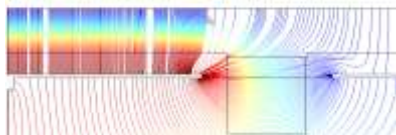
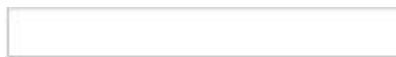
Many different tools have to work together



DVC CAD Tool at Cell Level

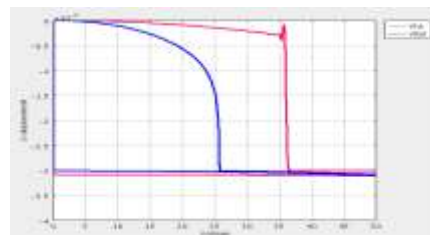
CELL DESIGN

Electrostatic
Simulation



CELL DESIGN

Electro-
mechanic
Simulation



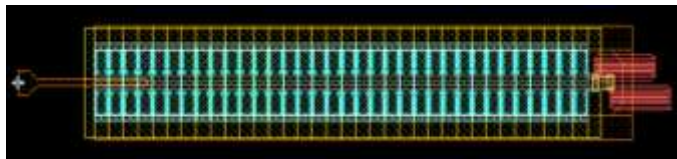
Crf-gnd, Crf-pi, Cpi-gnd,
Ccap-gnd, ...Cratio

Vpi, Vhs, Vrel, Vpu

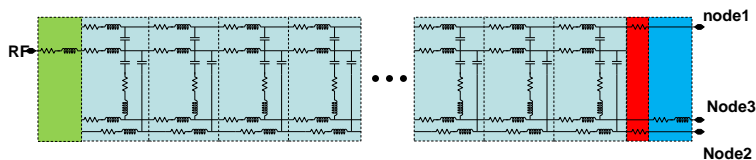
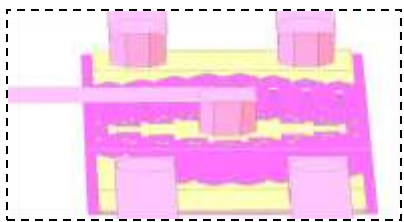
Cell design requires different simulators



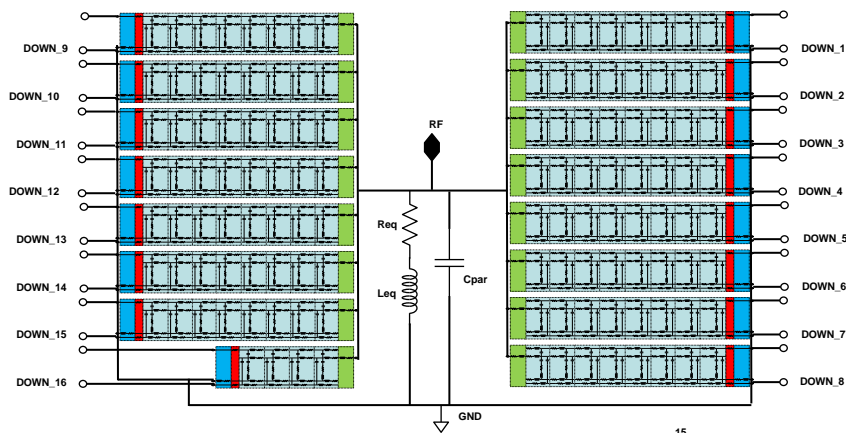
DVC CAD Tool at Array/Chip/Package levels



Package R,L,C



Interconnect R,L,C

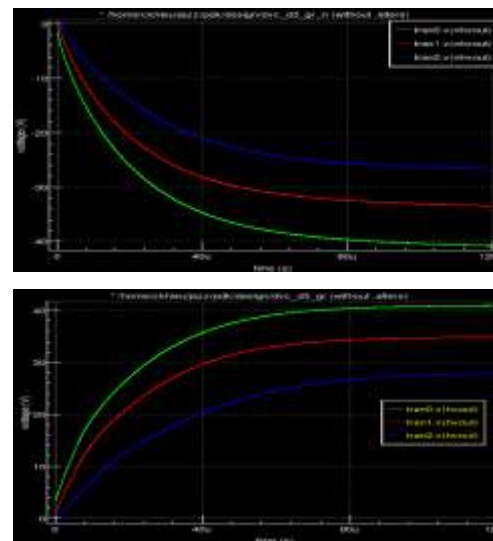
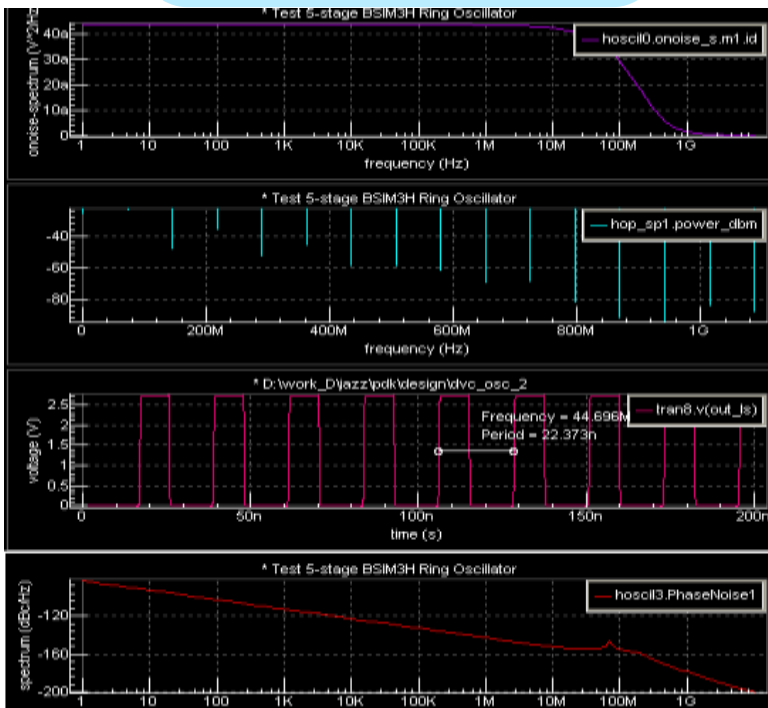




DVC Circuit/RF simulators

**Charge Pump
DESIGN
RF Simulator**

**Charge Pump
DESIGN
Circuit Simulator**



Pnoise, noise, harmonics

**posHV, negHV
Power, timing, S-paramaters**



Summary

- ❖ **RF front end limits the cell phone scalability to many bands**
- ❖ **MEMS provide solutions for:**
 - Antenna tunable matching network, or band select
 - High power handling, Very linear, no harmonics, low cost
- ❖ **MEMS + CMOS CAD Flow requires:**
 - Many different CAD tools and sometimes manual edits are required
 - There are room for CAD Design Flow Improvement